

Introduction & Methods

Non-Volatile Memory (NVM) devices are promising candidates for highly efficient Artificial Neural Networks (ANNs) [1]. However, the manufacture of NVMs is still to be developed. Several experimental examples have been successfully reported [2,3], but most of them rely on filamentary formation.

In this framework, ferroelectric-like memristive devices appear as an adequate alternative, specially when Transition Metal Dichalcogenides (TMDs) are employed in such devices [4]. In this work, we simulate and study the performance of MoS₂-based ferroelectric-like memristive devices.

Numerical simulation

Device simulations comprise the self-consistent solution in two dimensions of the Poisson equation along with the pseudo-Fermi energy level-based continuity equation for electrons and holes, and the ion drift-diffusion equation:

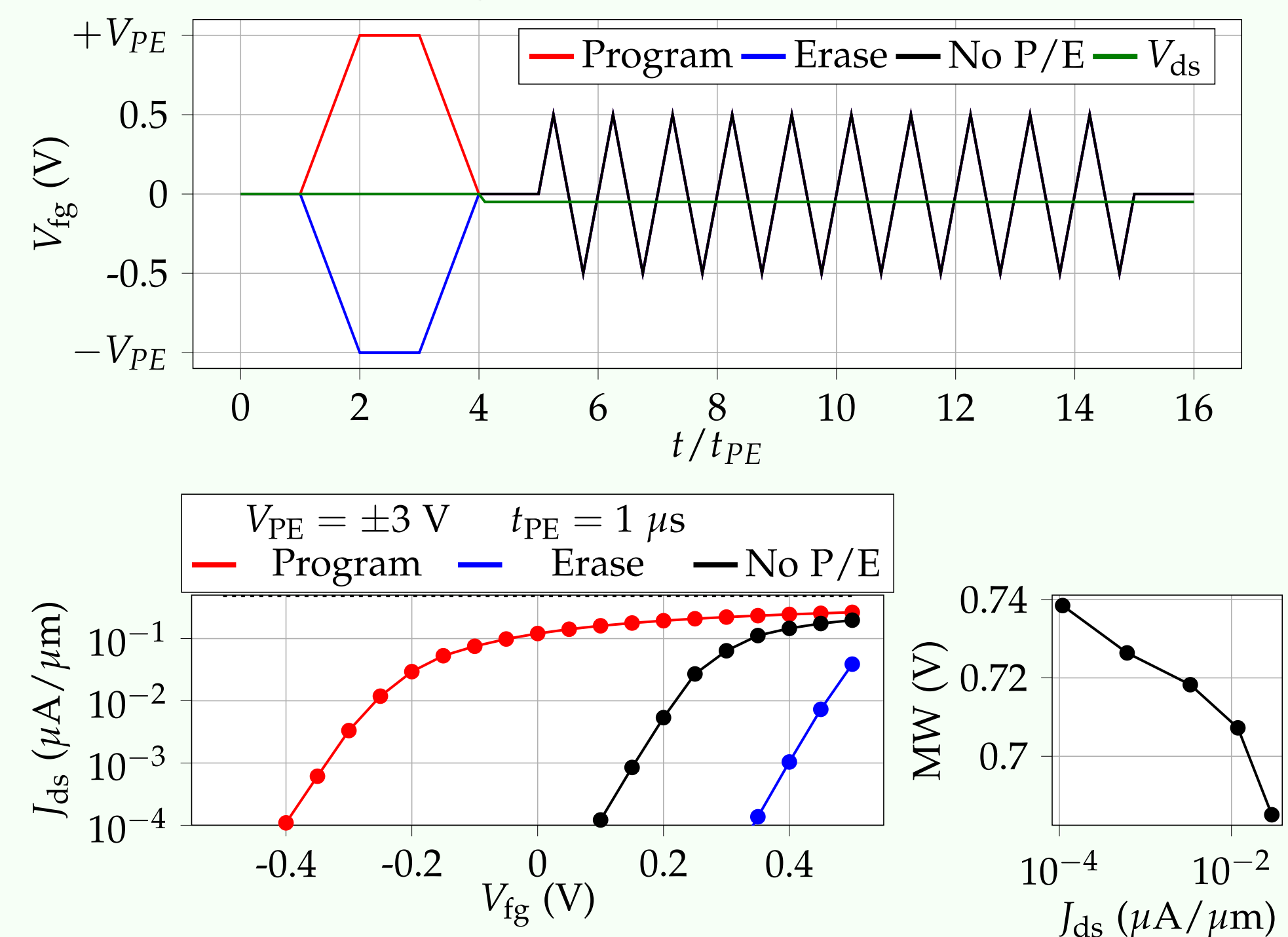
$$\nabla^2 V = -\frac{\rho}{\epsilon}$$

$$\begin{cases} \vec{\nabla} \cdot \vec{J}_n = \vec{\nabla} \cdot [q\mu_n n \vec{\nabla} E_{F,n}] = +q \frac{\partial n}{\partial t} \\ \vec{\nabla} \cdot \vec{J}_p = \vec{\nabla} \cdot [q\mu_p p \vec{\nabla} E_{F,p}] = -q \frac{\partial p}{\partial t} \end{cases}$$

$$\vec{\nabla} \cdot \vec{J}_i = \vec{\nabla} \cdot [-z_i q D_i (\vec{\nabla} c_i + s_i c_i \vec{\nabla} V)] = -z_i q \frac{\partial c_i}{\partial t}$$

- Program/Erase:** the P/E signal is a positive/negative square pulse applied at the gate contact at a constant $V_{ds} = 0$ mV. Mobile oxygen ions ($z = -2$) and vacancies ($z = +2$) drift across the top-gate oxide in opposite directions, inducing a change in the threshold voltage and the channel conductivity. After that, a $V_{fg} = 0.5$ V triangular Read signal is applied at a constant $V_{ds} = -50$ mV.

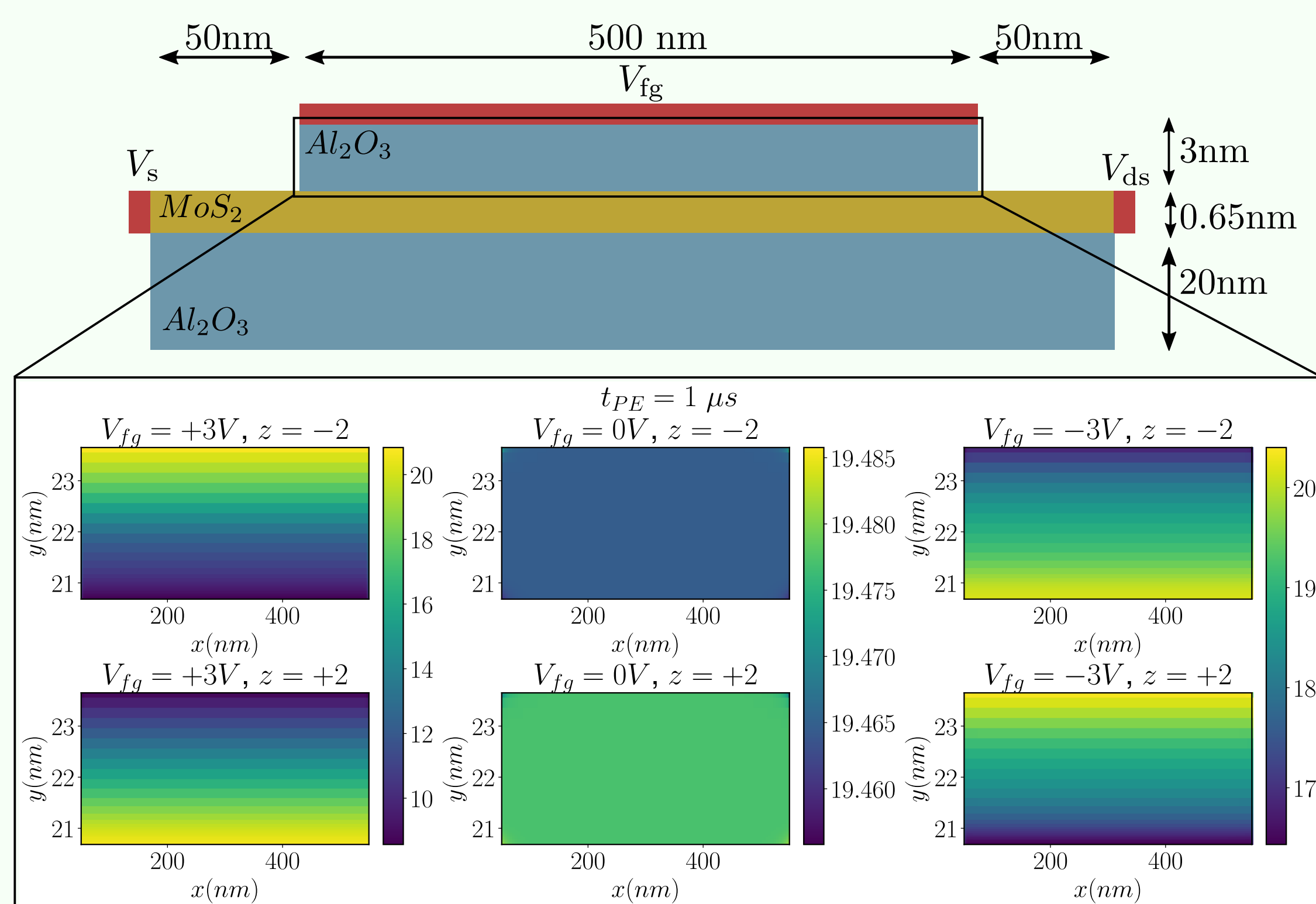
- Memory Window:** the device memory window (MW) is defined as the difference between the V_{fg} values needed to obtain a current density $J_{ds} = -0.01 \mu\text{A}/\mu\text{m}$ after applying P/E pulses.



Results

The simulated device consists of a monolayer MoS₂-based MOSFET with a 500nm-long channel. The gate insulator is a 3nm-thick Al₂O₃ layer. The electron and hole mobility is set to $\mu_{n,p} = 50\text{cm}^2/(\text{Vs})$.

- Mobile oxygen ions and vacancies are set in the gate-oxide with a mobility of $\mu_i = 2 \cdot 10^{-8} \text{cm}^2/(\text{Vs})$ and a uniform initial concentration of $c_0 = 3 \cdot 10^{19} \text{cm}^{-3}$.
- The amplitude, V_{PE} , and duration, t_{PE} , of the P/E signal determines the polarization of ions.



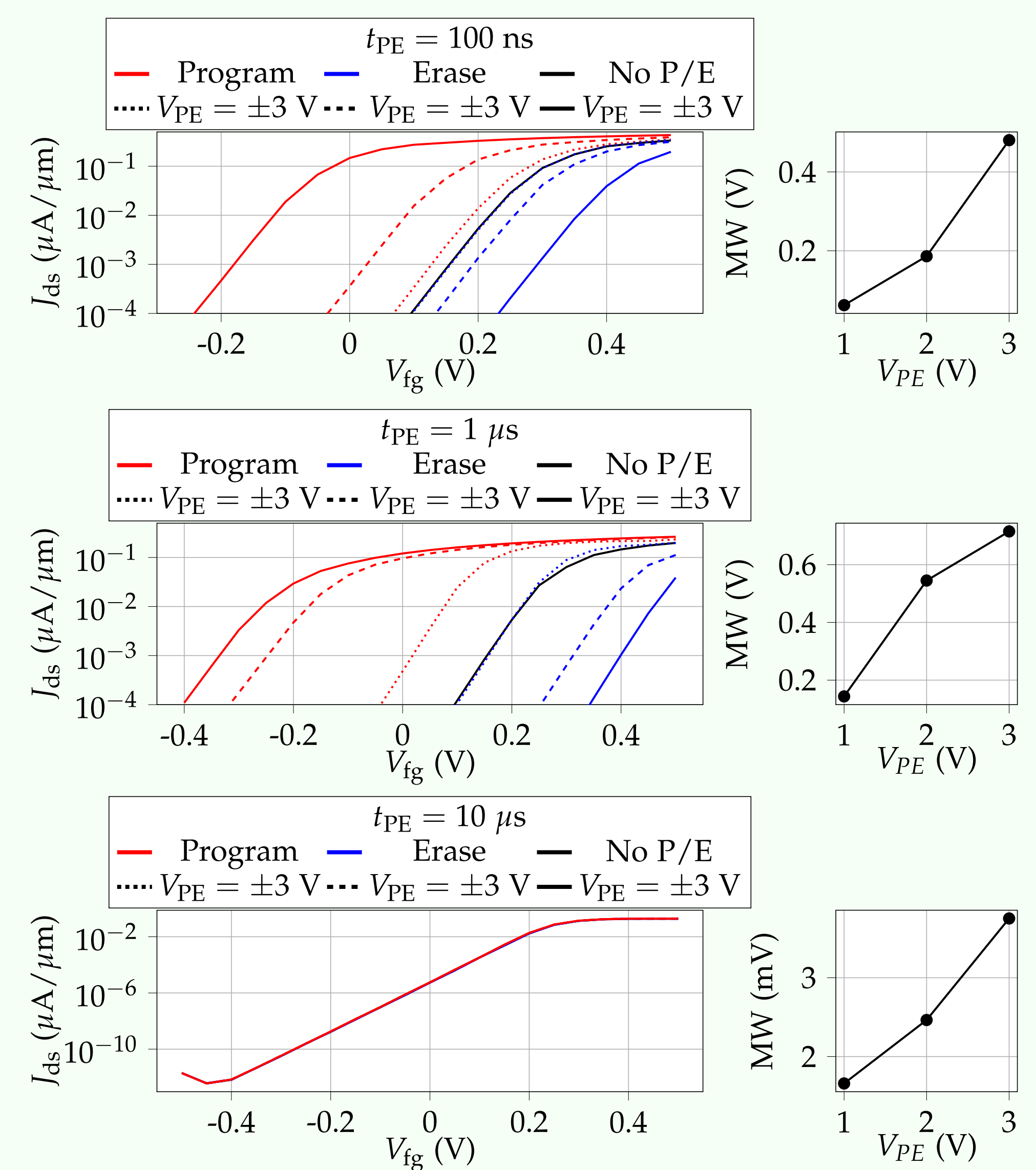
The device MW is analysed for P/E signals with different amplitude, $V_{P/E} = \pm 1\text{V}, \pm 2\text{V}, \pm 3\text{V}$, and duration, $t_{PE} = 100\text{ns}, 1\mu\text{s}, 10\mu\text{s}$.

A higher V_{PE} produces a larger modulation of the channel conductivity.

- For a given t_{PE} , the higher the V_{PE} , the greater the shift of the threshold voltage.
- In some cases, $V_{PE} = -1$ V seems to barely affect the output current.

The P/E duration, t_{PE} , is tightly related to the width of the MW.

- For a short P/E pulse, $t_{PE} = 100$ ns, ions have not enough time to drift. Thus, the resulting MWs are narrow.
- For a long P/E pulse, $t_{PE} = 1 \mu\text{s}$, ions distribute across the gate-oxide layer, producing wide MWs.
- For a large enough frequency, $t_{PE} = 10 \mu\text{s}$, ions polarize the gate-oxide, but they also follow the Read signal without delay, reversing the P/E situation and yielding negligible MWs.



Conclusions

- We introduced a self-consistent numerical tool for the simulation of 2DM-based ferroelectric-like memristive devices.
- The application of gate voltage pulses polarize the mobile ions inside the gate-oxide layer, thus shifting the transfer characteristic.

- A large V_{PE} is required to obtain high MW values up to 0.715 V.
- Both a short and a long t_{PE} can reduce the width of the MW, whether if ions do not polarize completely, or if the Read signal changes their distribution.

References

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